

# Ultraviolet Semiconductor Materials for Next-Generation Water Security

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*Org. 01123*

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J. J. Wierer, N. A. Modine and A.F. Wright*

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# Water Security



**Key Aspect:** Robust water quality assurance  
(*terrorist attacks, natural disasters, etc*)

**Potential Strategy:**

Supplement centralized water treatment facilities with distributed point-of-entry (POE) and point-of-use (POU) systems\*

**Desired Attributes:**

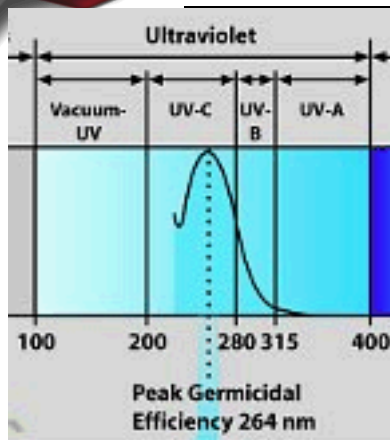
- broadly effective (*biological, chemical*)
- high reliability, low maintenance
- low cost, low energy consumption
- low environmental impact ( *manufacture, use, disposal*)

**Attributes for New Functionality:**

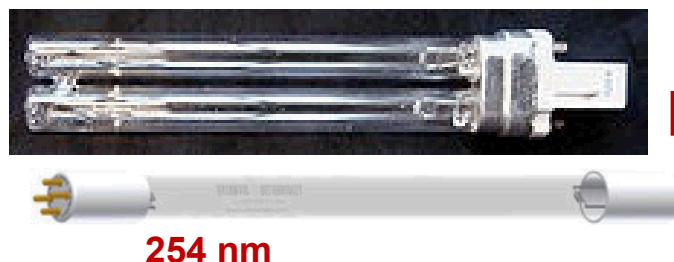
- no power requirements or solar-powered
- “smart” integration of sensing and purification functions
- communication between networked POE/POU systems

\*I. Silverstein, EPA Feb. 2006    Figures from EPA    [water.epa.gov/infrastructure/water security](http://water.epa.gov/infrastructure/water_security)

# Next-Generation UV Sources for Water Purification



Hg Lamps → Solid-state (LEDs)



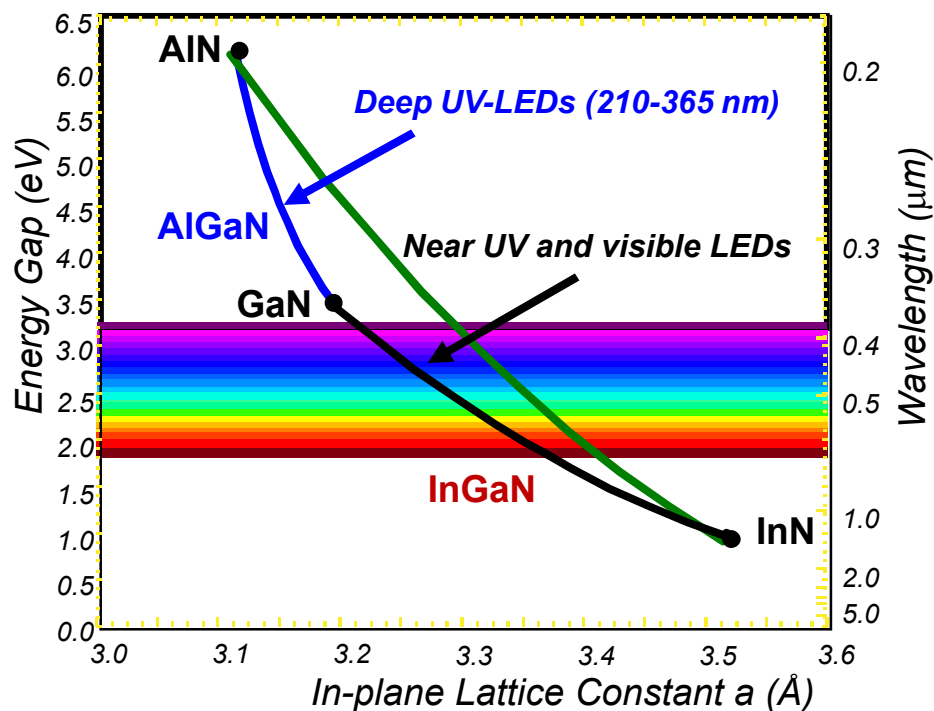
## UV LED Advantages:

- Avoids hazards of Hg disposal
- Integration with control electronics
- Low power / solar power
- Instant turn-on
- Wavelength tunable (340 nm / 265 nm for fluorescence sensing/purification)

## Limitations:

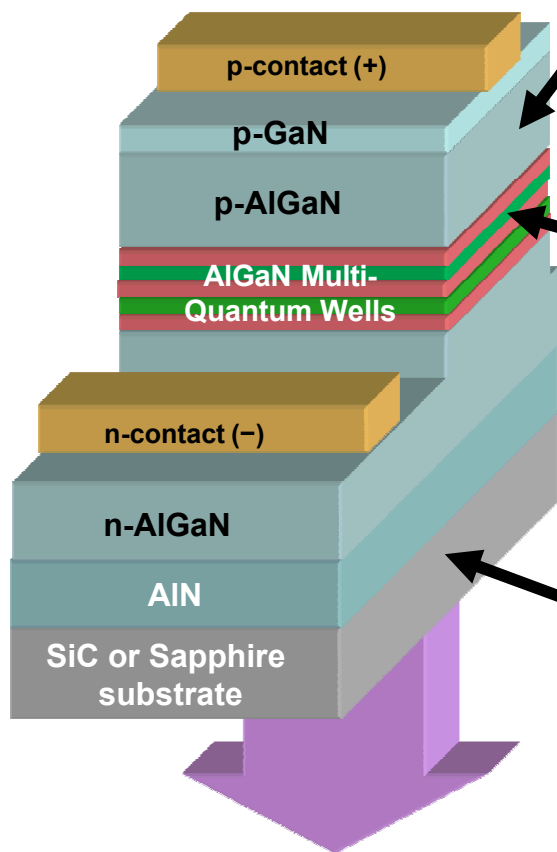
- Present devices only ~2% efficient
- Estimate > 10% efficiency is needed for practical implementation
- **Materials breakthroughs needed!**

## AlGaInN Semiconductor System



# Materials challenges for realizing high performance AlGaN deep UV LEDs

## AlGaN Deep UV LED (p-n junction device)



### p-type AlGaN is very difficult

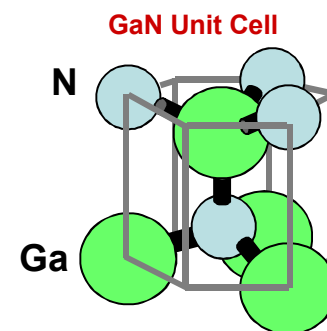
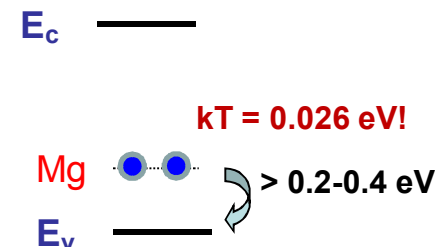
- Large acceptor ionization energies
- Compensating defects
- P-GaN is better, but absorbs deep-UV!

### AlGaN Quantum Wells have low optical efficiency

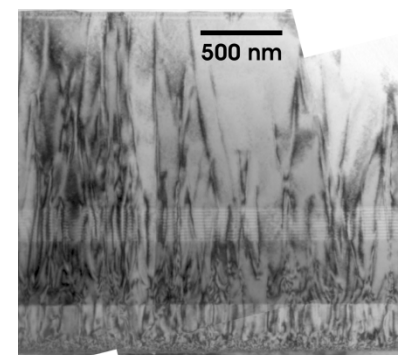
- Non-radiative crystalline defects (e.g., impurities, vacancies)

### Lack of AlGaN Substrates

- high densities of extended defects (threading dislocations)  $> 10^9 \text{ cm}^{-2}$
- Reduced device efficiency and operational lifetime



TEM image of AlGaN on sapphire

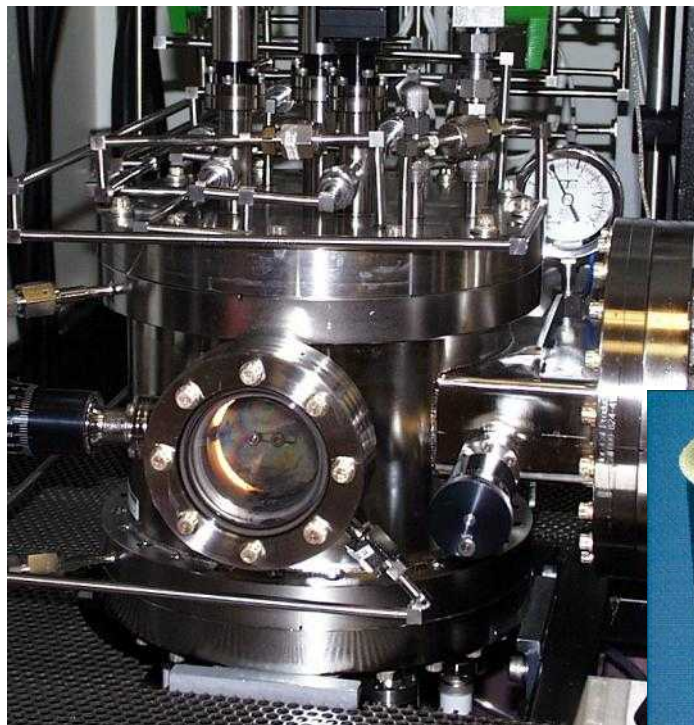


Sapphire substrate

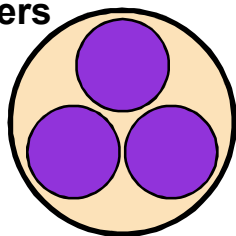


# Epitaxial Growth of Nitride Semiconductors by Metal-organic Vapor Phase Epitaxy at Sandia

## Veeco D-125 Rotating Disk MOVPE System



3 two-inch wafers



## AlGaIn Growth

Sources: TMGa, TMAI,  $\text{NH}_3$

Temp:  $1035\text{--}1100^\circ\text{C}$

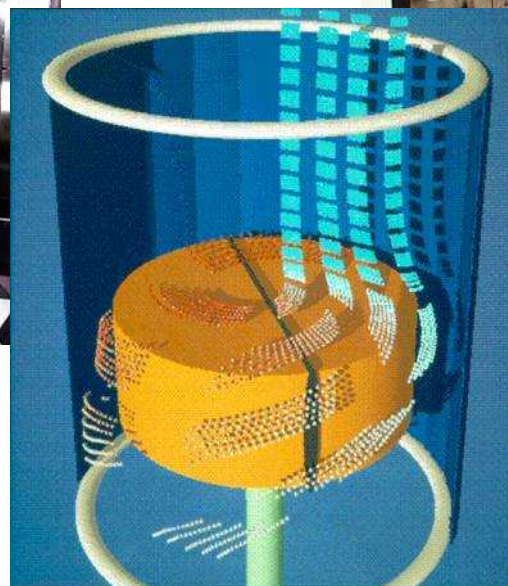
Pressure: 75-300 torr

Growth rates:  $0.3\text{--}1\ \mu\text{m}/\text{hour}$

## Dopants:

n-type:  $\text{SiH}_4$

p-type:  $\text{Cp}_2\text{Mg}$



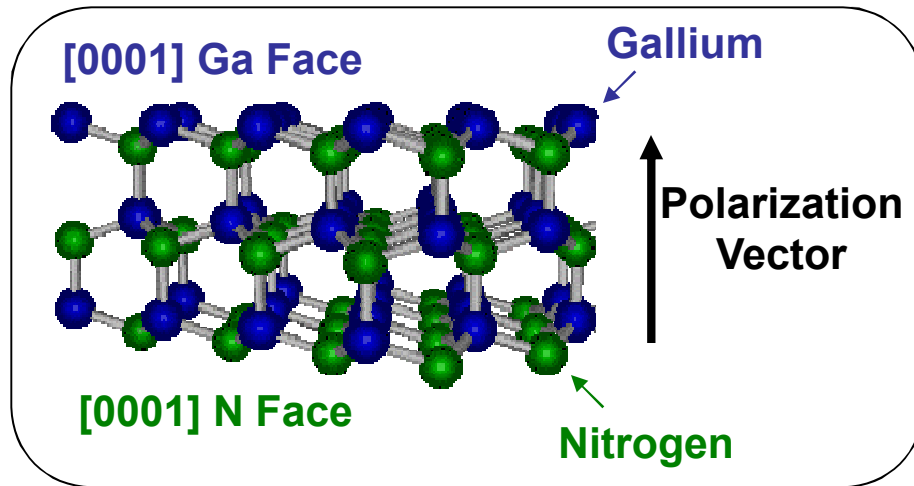
Rotation  $\sim 1500\ \text{rpm}$



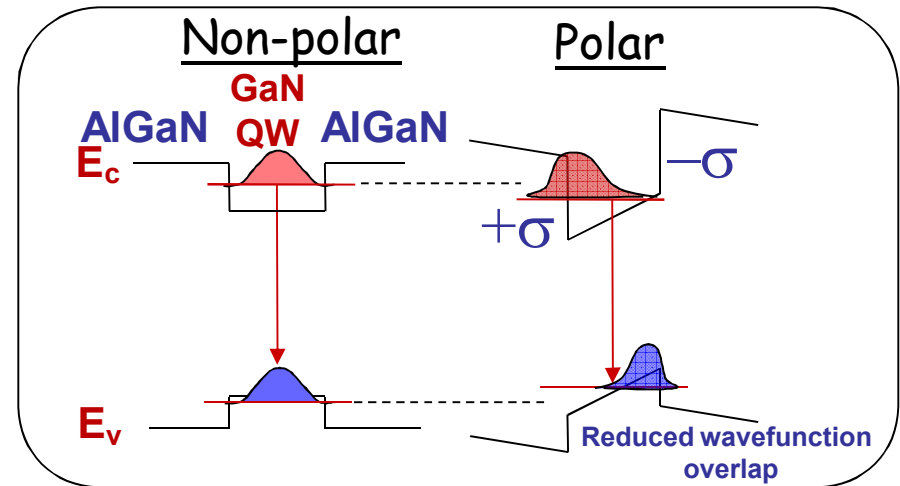
Andrew Allerman,  
Org. 01126

# Proposed P-type Doping Solution: Mg-doped Short-Period Superlattice

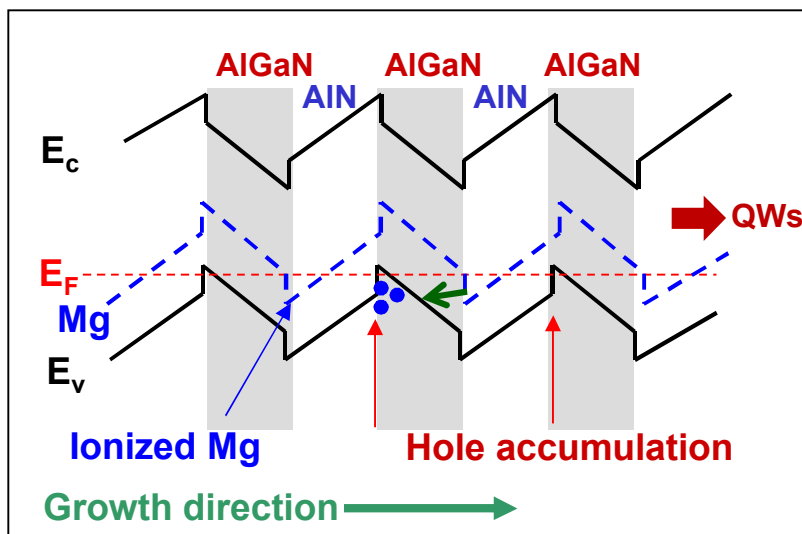
## Wurzite GaN crystal structure



## Polarization effect on GaN quantum well



## Mg-doped Polarization Superlattice



- Manipulation of polarization fields alters electronic states and enables hole accumulation
- Use of “ultrathin” layers (5-15Å) in the SL enables:
  - high effective bandgap of random alloy (Al~0.60)
  - possibility of tunneling-assisted vertical transport

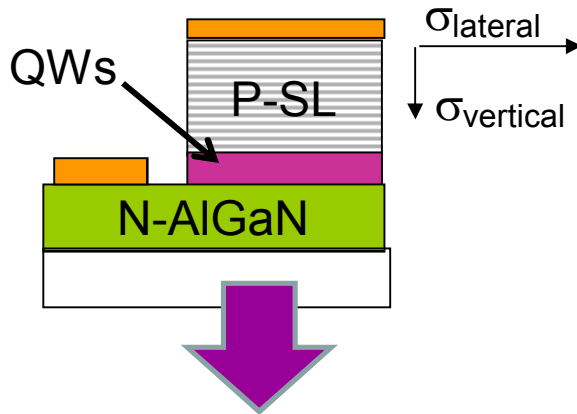


**Deep-UV-Transparent  
Hole Injector**

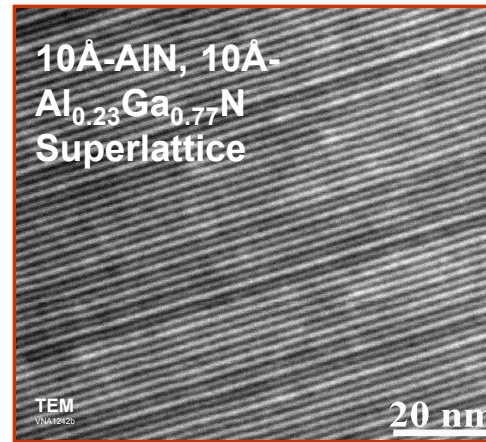
Nikishin et al  
JAP (2005)  
(MBE growth)

# Progress to Date on Mg-doped SPSLs

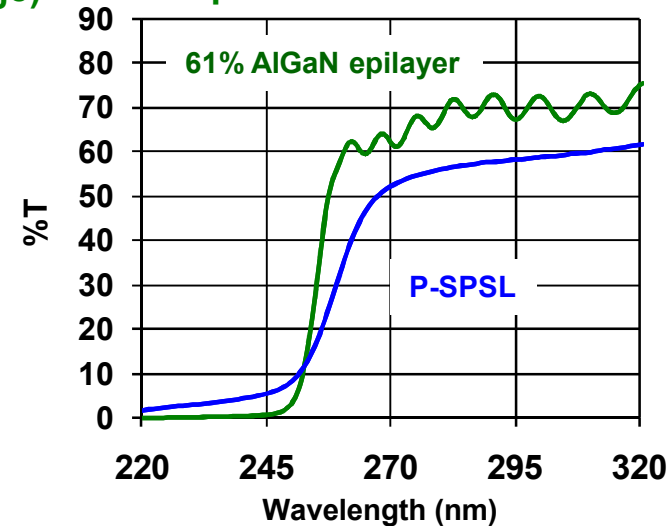
## Proposed p-SPSL LED



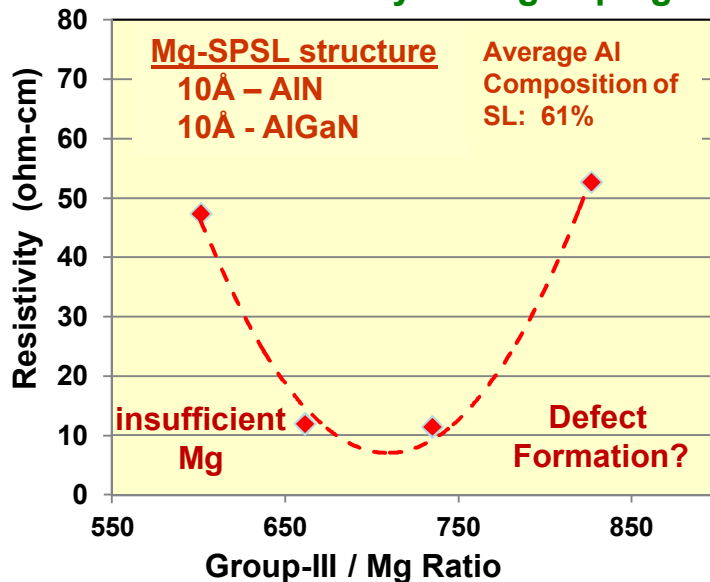
## Structural Properties (TEM image)



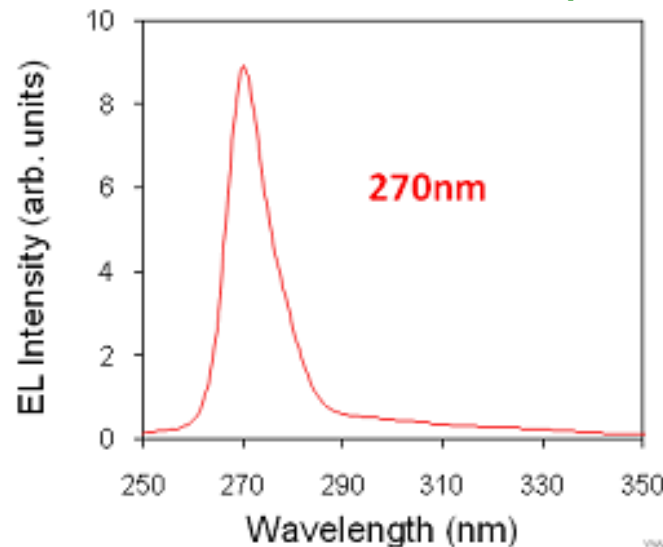
## Optical Transmission



## Lateral resistivity vs. Mg doping level



## Electroluminescence from p-SPSL LED



Improvement of vertical conductivity still needed

A. A. Allerman et al,  
J Crystal Growth,  
(2010)

# Application of Novel Tools to Study Point Defects

## Motivation

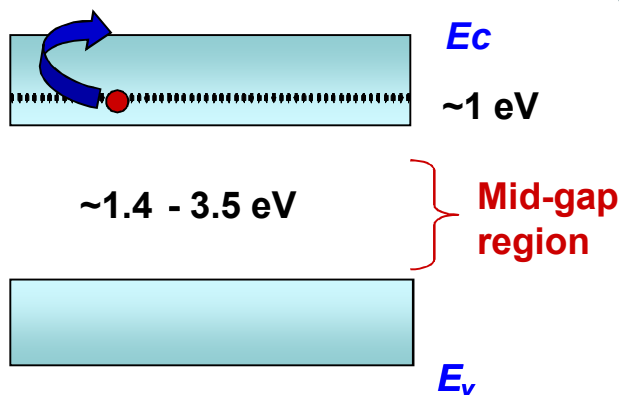
- Point defects (*vacancies, impurities, etc.*) may cause non-radiative recombination, dopant compensation, defect-assisted carrier tunneling from active region

## Challenge

- Most common experimental techniques (e.g., DLTS) can't probe entire bandgap

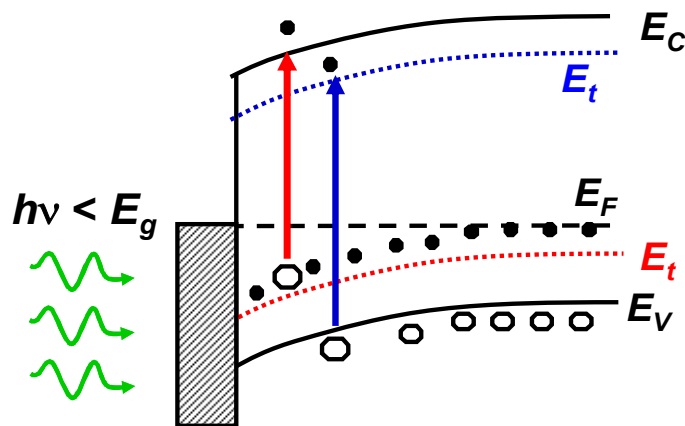
## Deep Level Transient Spectroscopy

Thermal emission of carriers from defect states



- limited to  $\sim 1$  eV of  $E_c$ ,  $E_v$
- cannot probe mid-gap non-radiative centers

## Deep Level Optical Spectroscopy



- photo-capacitance technique
- application of tunable light excitation to access entire bandgap



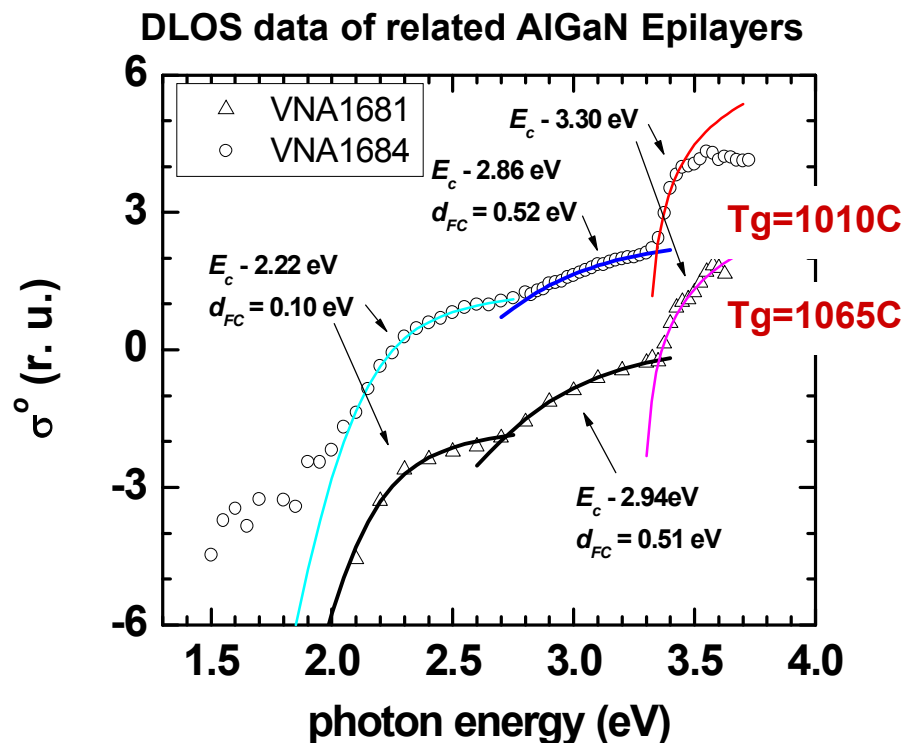
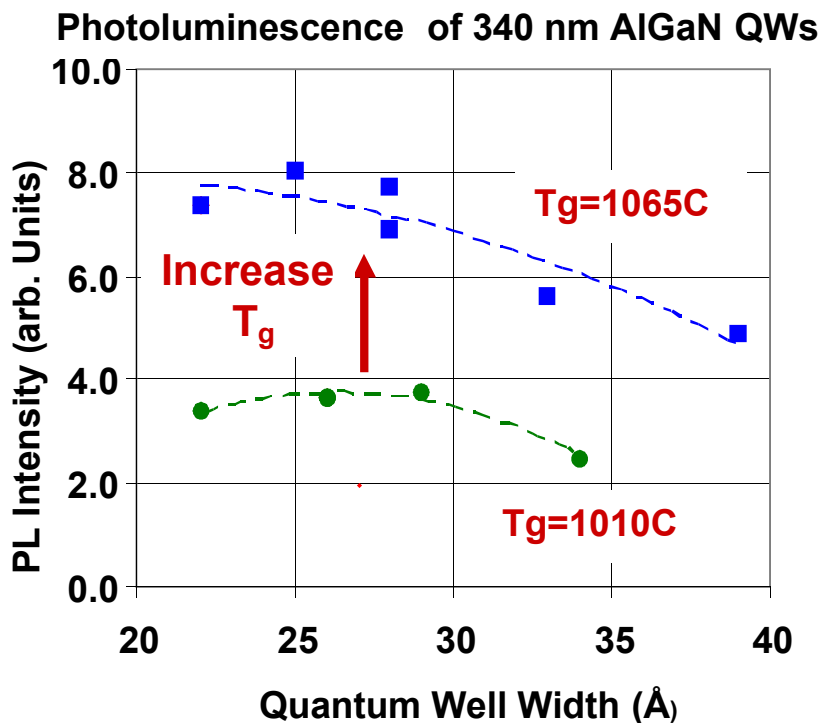
# Combination of photoluminescence and DLOS to study impact of QW growth temperature

Materials Growth Conditions

Defect Properties

Materials Performance

## Impact of growth temperature on AlGaIn quantum well luminescence



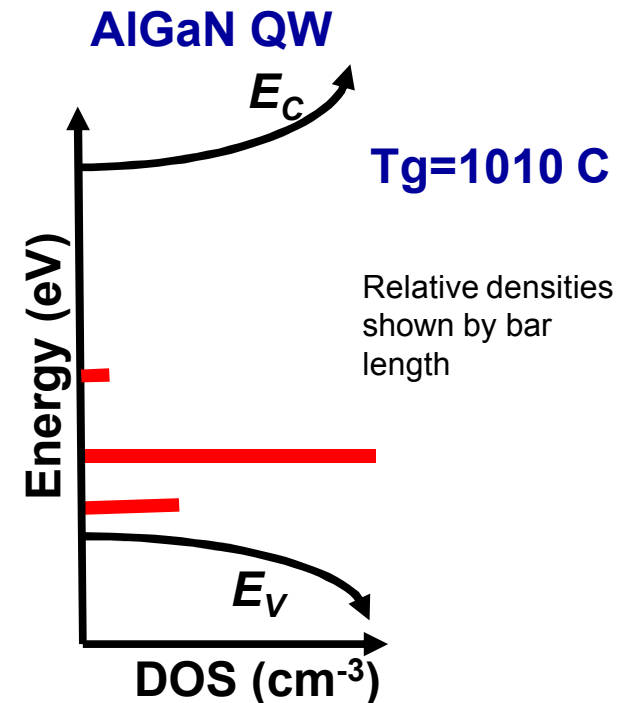
→ Change in growth temp does not introduce new defect levels

# Combination of photoluminescence and DLOS to study impact of QW growth temperature

Lighted CV measurements to determine densities of deep levels ( $\text{cm}^{-3}$ )

Trap Energy	Tg 1065°C	Tg 1010°C	Change
Ec-2.22 eV	2.5e15	1.1e16	4.4X
Ec-2.90 eV	2.7e16	9.0e16	3.3X
Ec-3.30 eV	7.7e15	3.0e16	3.8X

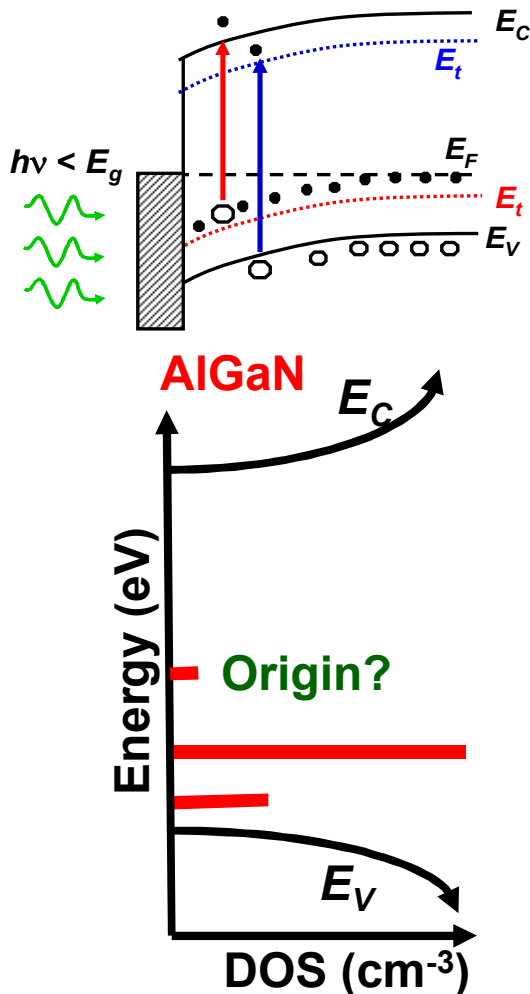
- ~3-4X increase in deep level density across the spectrum with lower Tg
- Increased defect density correlated with ~3X decrease in PL deep level intensity



**First quantitative correlation of AlGaIn growth conditions, increased deep level densities, and lower luminescence intensity**

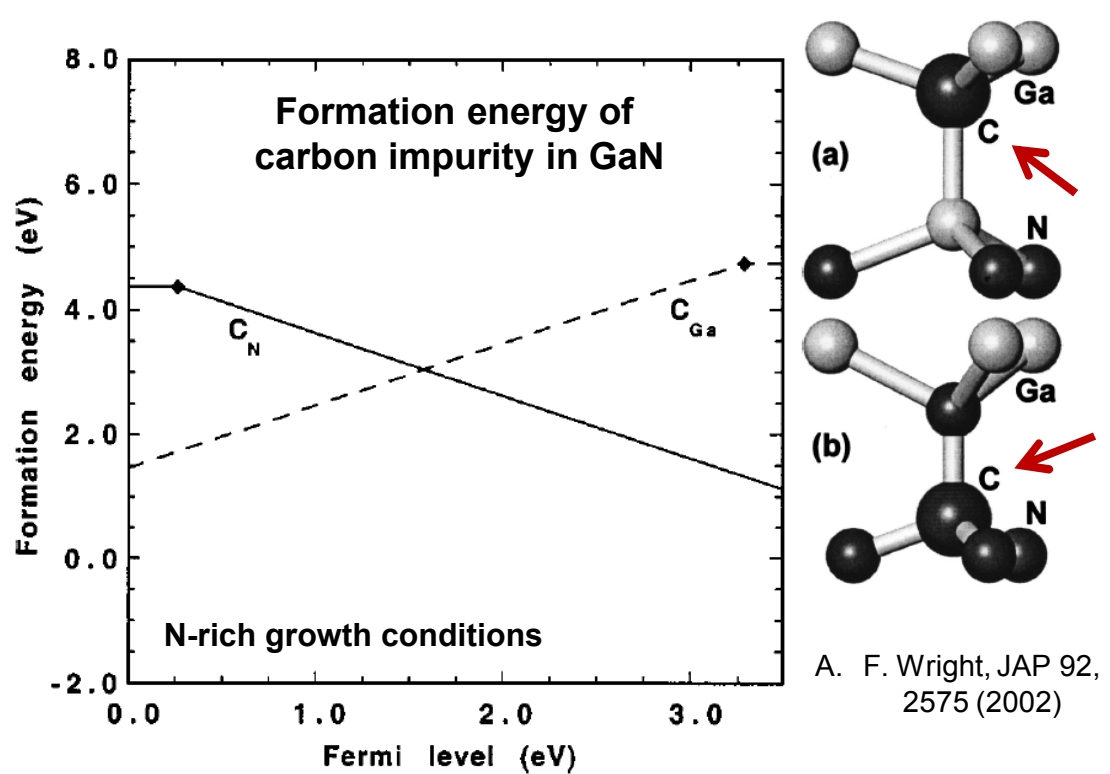
# Identification of physical origin of defect levels: Experiment and Theory

## Experiment: DLOS



Andy Armstrong (01123)

## Theory: Density Functional Theory

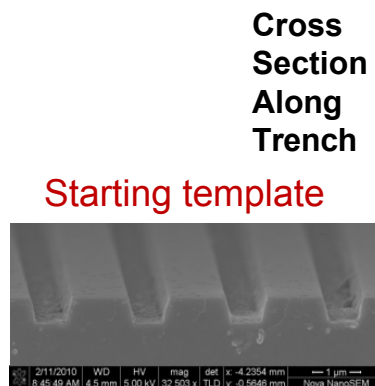
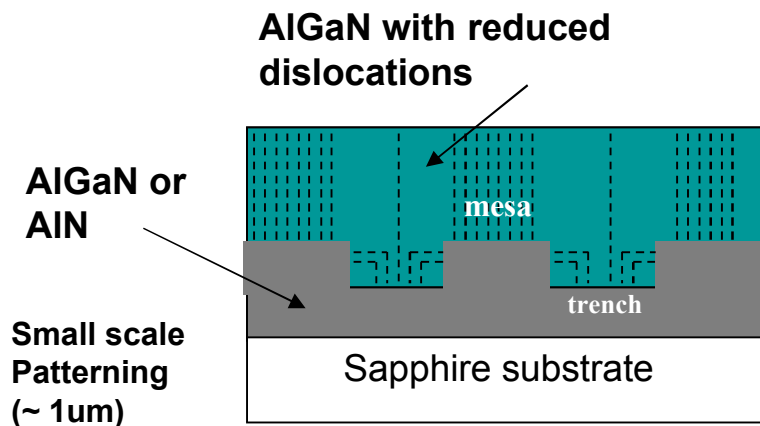


- Formation energies of defects
- Energies of defect levels
- Capture cross-sections

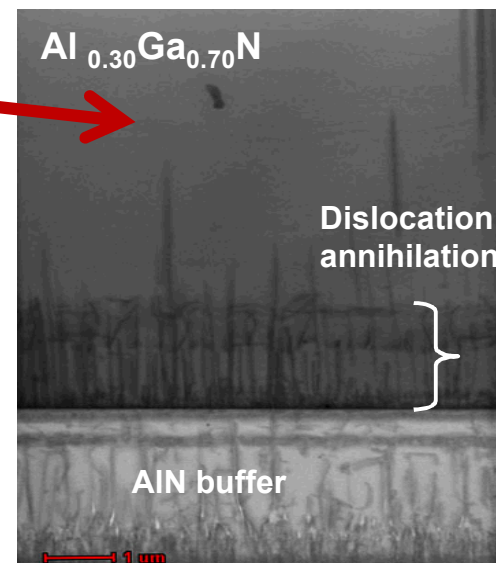
Alan Wright (01112)  
Normand Modine (01132)

# Materials Engineering for Mitigation of Extended Defects

## AlGaN Growth on Corrugated Templates

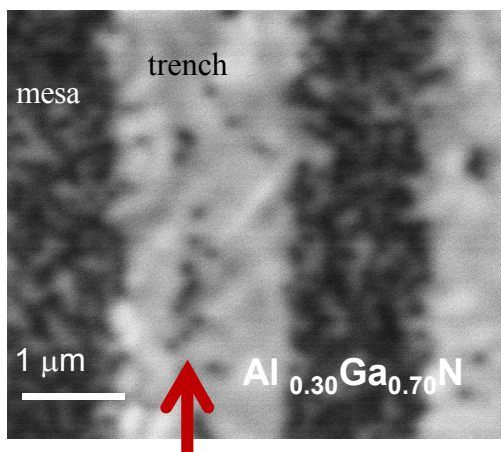


## TEM of AlGaN Epilayer

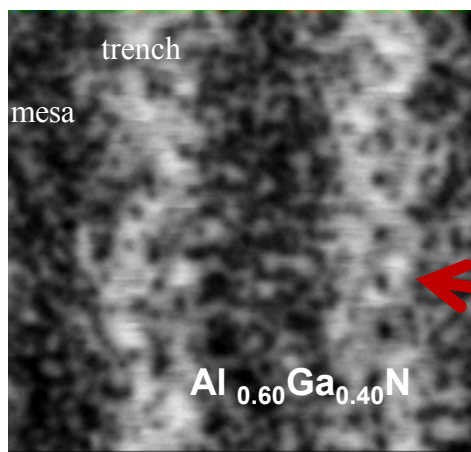


- Dislocations largely annihilated in ~1.5 microns of growth!

## CL of 340 nm AlGaN QWs



## CL of 280 nm AlGaN QWs



Demonstration of viability in germicidal region (< 300 nm)

- 10-30X TD reduction in Al<sub>0.30</sub>Ga<sub>0.70</sub>N (340 nm), to 2-4 e8 cm<sup>-2</sup> in trenches

A. Allerman

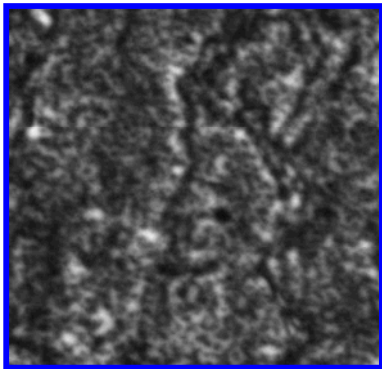
Iida et al., J. Crystal Growth (2007)  
Kueller et al., J. Crystal Growth (2010)



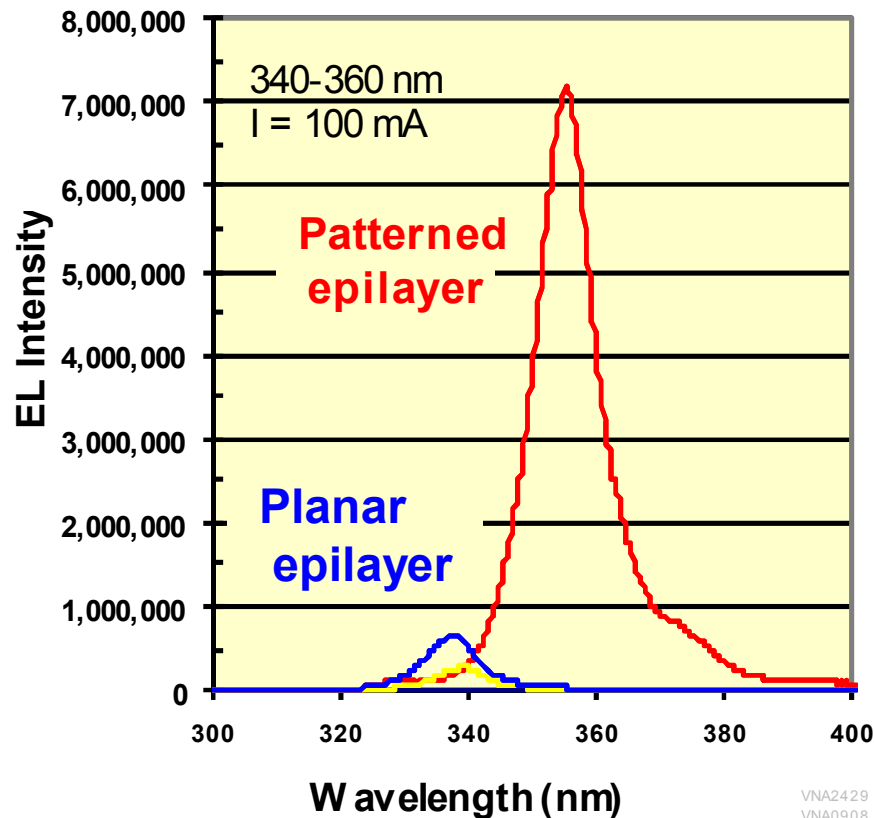
# Impact of Dislocation Reduction

## Electroluminescence of p-n Junction structure

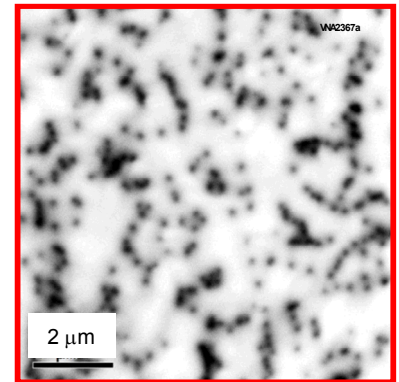
CL from planar  
AlGaIn epilayer



$\text{Al}_{0.30}\text{Ga}_{0.70}\text{N}$   
No patterning



CL from patterned  
AlGaIn epilayer



$\text{Al}_{0.30}\text{Ga}_{0.70}\text{N}$

- 10x increase in LED emission with patterned AlGaIn template!
- Improved CL (reduced dislocations) leads to improved EL
- Presently working toward implementation in deeper UV LEDs



# Summary

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**Goal:** develop novel UV sources based on LEDs to enable point-of-use water purification systems with enhanced capabilities

- Requires overcoming major materials challenges of AlGaIn alloys, Including fundamental limitations to p-type doping, and the effects of point and extended defects
- Developed Mg-doped polarization superlattices as a means to circumvent thermal activation of p-type dopants and achieve hole Injection with a deep UV transparent structure; 1<sup>st</sup> generation LEDs with emission in the germicidal region
- Applied DLOS to achieve new insights into the correlation of AlGaIn growth conditions, defect properties, and materials performance; potential to understand and control defect populations
- Advancing patterned-growth defect-reduction approaches to higher Al-content AlGaIn devices, relevant to germicidal region of the spectrum